Attorney Docket No.: FIS920030352US1

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re PATENT APPLICATION Of:

Tien-Jen Cheng et al.

Appln. No.: 10/707,892 | Art Unit: 2815

Filed: January 21, 2004 Examiner: M. C. Landau

For: DEVICE WITH PROBABLE AREA

ARRAY PADS

DECLARATION UNDER 37 C.F.R. §1.131

Mail Stop **AMENDMENT** Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

We, Tien-Jen Cheng, David E. Eichstadt, Jonathan H. Griffith, Sarah H. Knickerbocker, Samuel R. McKnight, Kamalesh K Srivastava, Kevin S. Petrarca, and Roger A. Quon, inventors for the invention claimed in the above referenced patent application, declare as follows:

Sometime prior to September 18, 2003, we conceived area array pads (hereinafter "Pads") that, when included on a device, such as a semiconductor device and/or structure, may be used for test probing the device;

Attached hereto and marked Exhibit A, is a copy of a presentation explaining our Pads, formation of the Pads, and test results of the Pads, all dates having been redacted therefrom, providing evidence of conception and reduction to practice:

As evidenced in pages 3 and 4 - 6 of Exhibit A, our Pads included:

- a terminal metal layer disposed on a passivating layer;
- a diffusion barrier layer on said terminal metal layer;
- a conducting layer pad on said diffusion barrier;

a hard test barrier layer on, and enclosing (see page 6 of Exhibit A), said conducting layer pad, wherein said hard test barrier layer extends along the sides of said conducting layer pad and said conducting layer pad is completely enclosed by said diffusion barrier layer and said hard test barrier layer; and

a plate passivating layer on said hard test barrier layer;

Sometime prior to September 18, 2003, we reduced our invention to practice as evidenced in pages 8 - 10 of Exhibit A;

All acts, including conception and reduction to practice, occurred in the United States;

We further declare that all statements made herein of our own knowledge are true and that all statements made on information and belief are believed to be true; and

We further declare that these statements were made with the knowledge that willful false statements and the like so made are punishable by fine or imprisonment, or both, under Section 1001 of Title 18 of the United States Code, and that such willful false statements may jeopardize the validity of the application or any patent issued thereon.

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Problem Statement:

No Technology or Method exists for testing device performance on area-array, non-compliant metallurgies.

- · Testing device performance directly on C4s is common practice, but is destructive
- Testing device performance on FBEOL via metallurgies is possible, but is also disruptive to bumping processes

Proposal

metallurgies which also serve as a C4 ball-limiting metallurgy for bumping A Means and Method for testing device performance on non-compliant after test.



Silicon Interconnect Advanced Process Technology

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R. Quon, S. McKnight, T. Cheng, D. Eichstadt, S.Knickerbocker, K. Srivastava, K. Petrarca, J. Griffith Silicon Interconnect Advanced Process Technology

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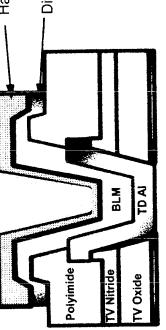
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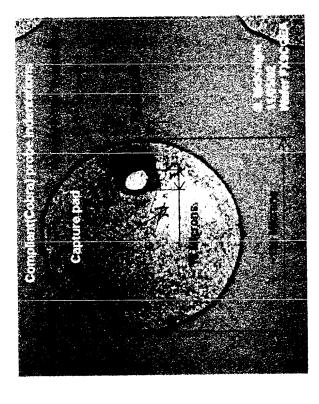
essential elements of a bump metallurgy for test

Passivating / Test Metallurgy (eg. Cu or Au)

— Hard Test Barrier (eg. Ni or Ti, refractory metals)

—— Diffusion Barrier (eg. Cr., TIW, Ti, Ta, TaN, AI)





bump metallurgy tested!

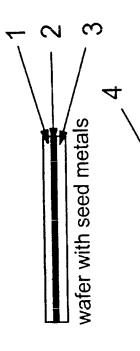
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【记述 technology Microelectronics Division Process Flow: Preferred Embodiment



structures

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block out mask

- seed metals commonly terminating in coppets
 barrier and/or adhesion metallurgy

 e.g. TiW, Ti, Ta, TaN, and so on.

 substrate

 patterned resist selectively blocking seed metal
 copper pad

 5. copper pad

selective seed etch

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Disclosure F

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Process Flow:

structures

8. Sub-etch the diffusion barrier to form the final stept test metallurgy.
While this method of constructing the test sign with the art of could clearly construct the test structure by other means, including, but not limited to thru-hole plating and metal evaporation. These techniques construction the spirit of this embodiment.

*[:]\\\\\ technology Microelectronics Division

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Sub-etch diffusion barrier



Invention and Advantages:

Enables MD Foundry

- Capability for wafer-level test prior to bumping offers customers more options for bumping and assembly
- Area-Array Testing on C4 UBM allow MD to track and optimize yields for Foundry Customers

Enhances Test Capability

- Improved signals for measurements as contact resistance between probe and non-compliant metallurgy is LOWER than typical.
 - ▶ Less force required to make good electrical contact ENABLES Multi-Die Testing from a force perspective
 - Less clean and prep work required REDUCES test cycles.

Enable Test Ability for Fine Pitch Designs

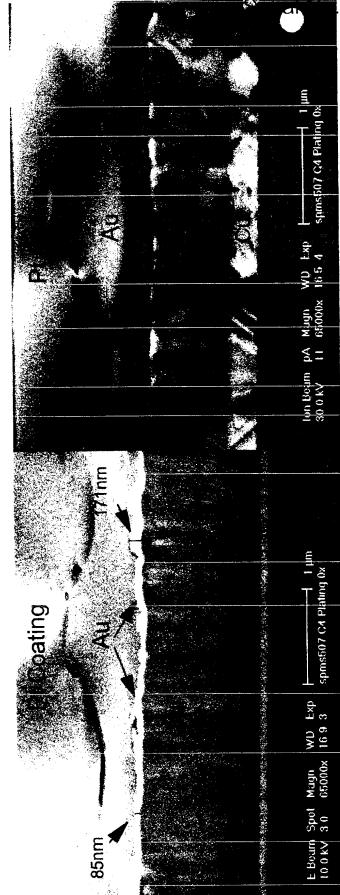
Testing on Pads precludes Deformation and Bulging of solder



C4 Plating BLM Layer Measurements

ASG FIB Analysis Electron Image

lon Image



0x REFLOWS

C4Plate_SPMS508_Capture Pad.PRZ

C4 Plating BLM Layer Measurements

lon Image Electron Image oating FIB Analysis ASG

3x REFLOWS

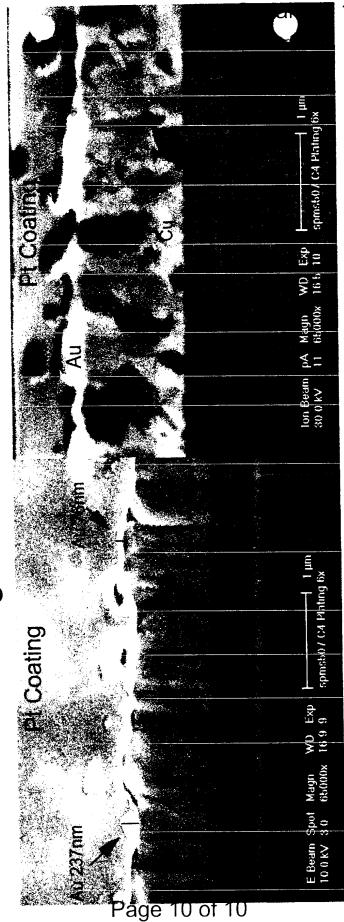
spms507 C4 Plating 3x

C4Plate_SPMS508_Capture Pad.PRZ

C4 Plating BLM Layer Measurements

ASG FIB Analysis Electron Image

lon Image



6x REFLOWS

FIS920030352US1 Serial No. 10/707,892

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